



[54] MOS TYPE SEMICONDUCTOR DEVICE HAVING A LOW CONCENTRATION IMPURITY DIFFUSION REGION

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[21] Appl. No.: 147,866

[22] Filed: Nov. 4, 1993

[30] Foreign Application Priority Data

Nov. 4, 1992	[JP]	Japan	4-294819
Nov. 4, 1992	[JP]	Japan	4-294820

[51] Int. Cl.⁶ H01L 29/76; H01L 29/94; H01L 31/062; H01L 31/113

[52] U.S. Cl. 257/369; 257/336; 257/344; 257/408

[58] Field of Search 257/408, 336, 257/344, 369

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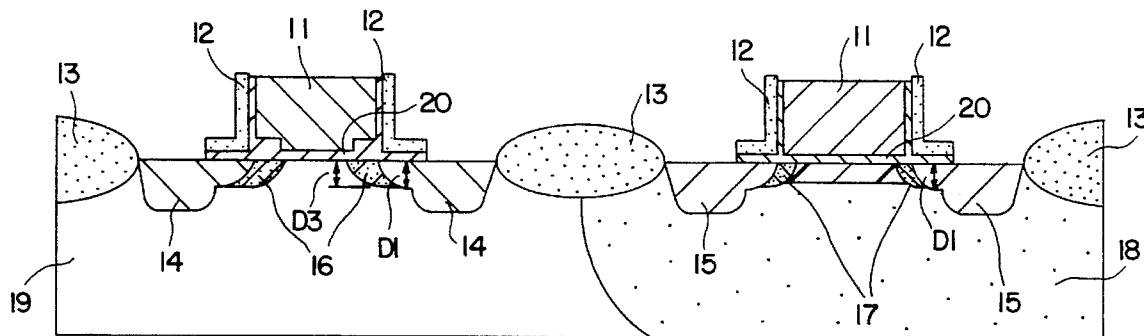
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[57] ABSTRACT

An MOS type semiconductor device comprises a semiconductor substrate including a p-type region doped with p-type impurities and having a surface and an MOS transistor formed in the p-type region, the MOS transistor including: an n-type source region formed in the p-type region; an n-type drain region formed in the p-type region and separated from the n-type source region by a predetermined distance; a channel region formed in the p-type region and located between the n-type source and drain regions; a pair of n-type impurity diffusion regions formed on both sides of the channel region and having an impurity concentration lower than that of the n-type source region; a gate insulating film formed on the surface of the semiconductor substrate, the gate insulating film directly covering the channel region and the pair of n-type impurity diffusion regions; a gate electrode formed on the gate insulating film; and side walls formed on the sides of the gate electrode, wherein each of the side walls has a bottom portion extending along the surface of the semiconductor substrate from each side of the gate electrode, and each of the n-type source and drain regions has a first portion covered with the bottom portion of the side wall and a second portion not covered with the bottom portion, a thickness of the first portion being smaller than that of the second portion. A method for fabricating such an MOS type semiconductor device is also provided.

5 Claims, 9 Drawing Sheets



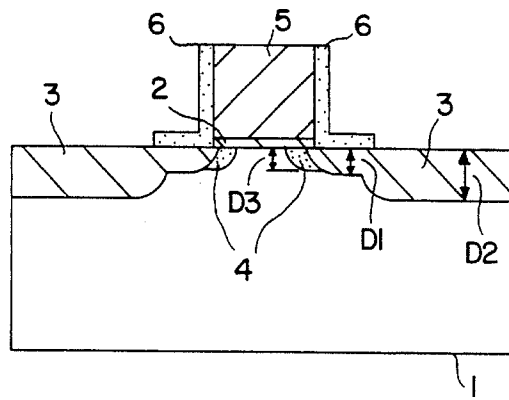


FIG. 1

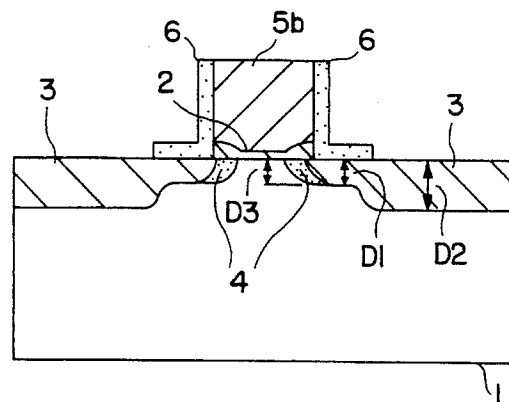


FIG. 2

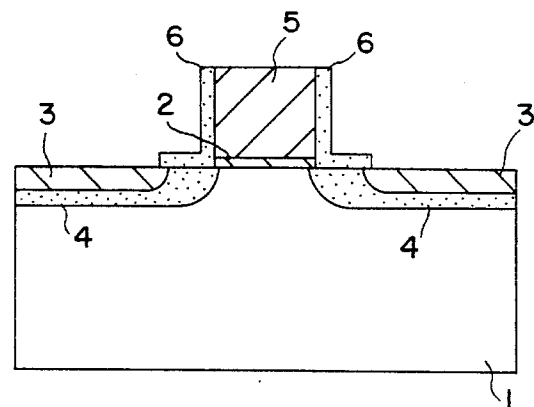


FIG. 3

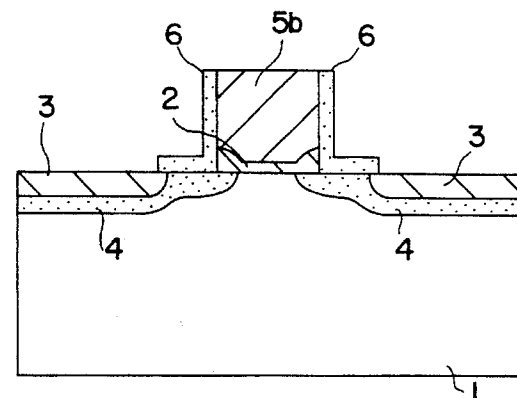


FIG. 4

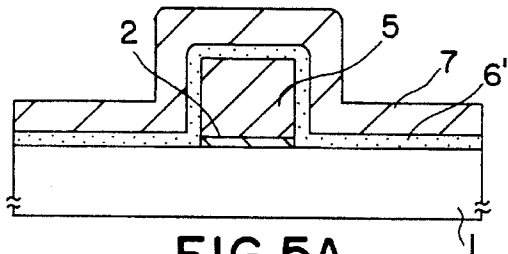


FIG. 5A

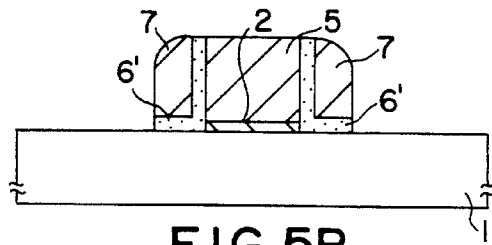


FIG. 5B

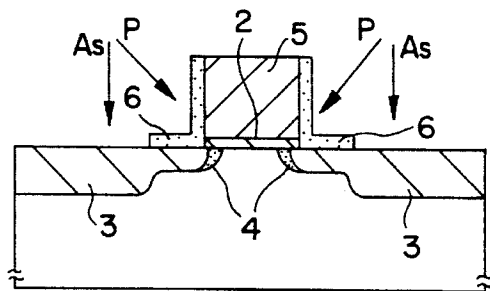


FIG. 5C

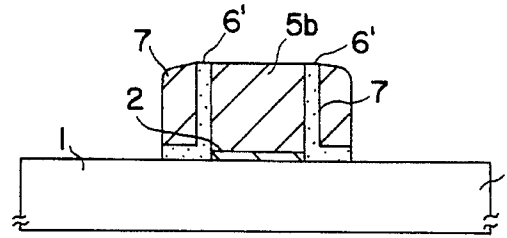


FIG. 6A

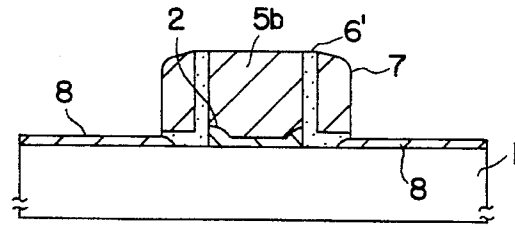


FIG. 6B

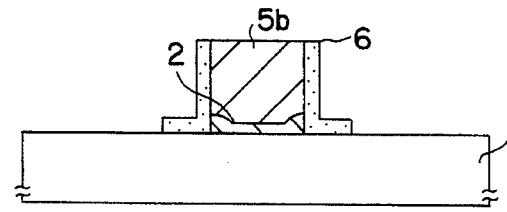


FIG. 6C

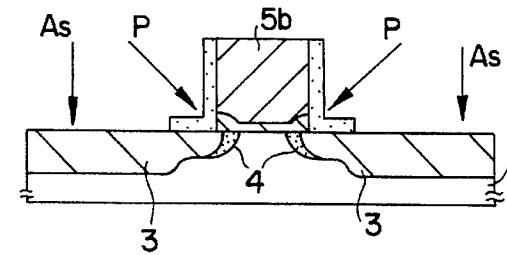


FIG. 6D

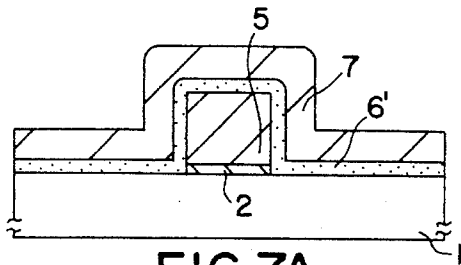


FIG. 7A

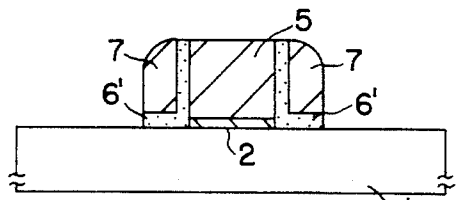


FIG. 7B

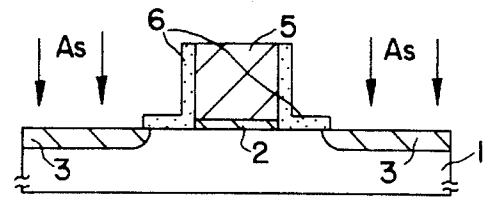


FIG. 7C

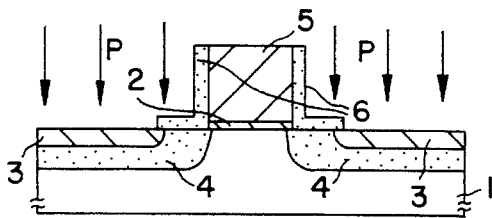


FIG. 7D

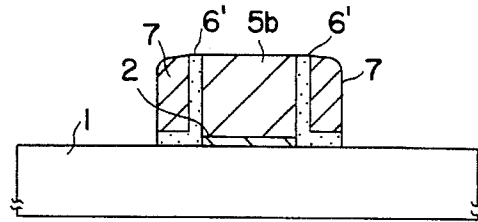


FIG. 8A

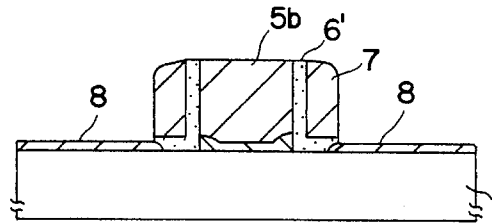


FIG. 8B

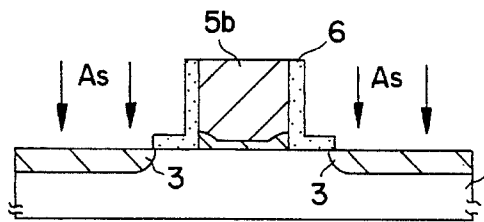


FIG. 8C

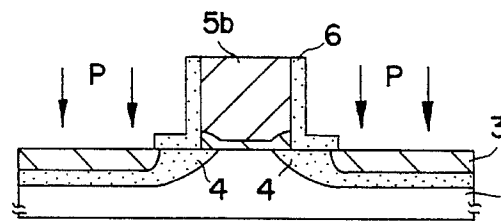


FIG. 8D

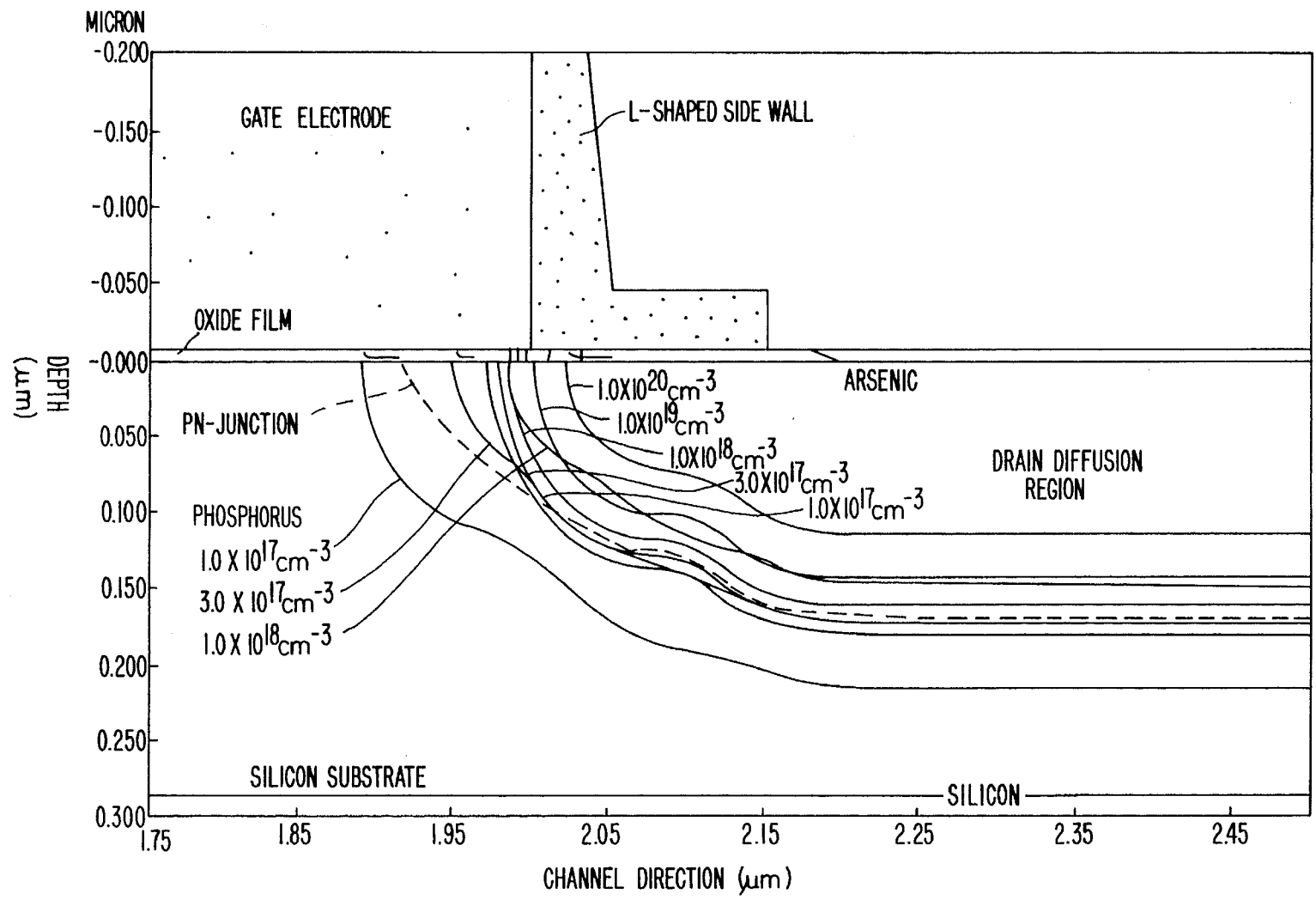


FIG. 9

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